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| Form PTO-1449 (modified) | Atty. Docket No. 2000.111200/H2022 | Serial No. Unknown 10/664 665 |
| List of Patents and Publications for Applicant's INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary) | Applicant Akram Ali Salman, Xuejun Zhao, Kurt O. Taylor and Stephen G. Beebe | |
| | Filing Date: September 18, 2003 | Group: Unknown 2813 |
| U.S. Patent Documents See Page 1 | Foreign Patent Documents See Page 1 | Other Art See Page 1 |

U.S. Patent Documents

| Exam. Init. | Ref. Des. | Document Number | Date | Name | Class | Sub Class | Filing Date of App. |
|-------------|-----------|-----------------|------|------|-------|-----------|---------------------|
| | A1 | | | | | | |
| | A2 | | | | | | |
| | A3 | | | | | | |

Foreign Patent Documents

| Exam. Init. | Ref. Des. | Document Number | Date | Country | Class | Sub Class | Translation Yes/No |
|-------------|-----------|-----------------|------|---------|-------|-----------|--------------------|
| | B1 | | | | | | |
| | B2 | | | | | | |
| | B3 | | | | | | |

Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

| Exam. Init. | Ref. Des. | Citation |
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| <i>AS</i> | C1 | Salman <i>et al.</i> , "Gate Dielectric Breakdown and Latent Failures of Ultrathin (~13A) DPN under Pulsed Stress in Partially Depleted SOI MOSFETs" |
| <i>AS</i> | C2 | Wu <i>et al.</i> , "Breakdown and Latent Damage of Ultra-Thin Gate Oxides under ESD Stress Conditions," EOS/ESD Symposium 00-287-295 |
| <i>AS</i> | C3 | Montoya <i>et al.</i> , "A Study of the Mechanisms for ESD Damage to Reticles," EOS/ESD Symposium 00-394-405 |
| <i>AS</i> | C4 | Hunter, "The Analysis of Oxide Reliability Data," 98 IRW Final Report, 114-34 |
| <i>AS</i> | C5 | Linder <i>et al.</i> , "Growth and Scaling of Oxide Conduction after Breakdown," 2003 IEEE, 402-05 |
| <i>AS</i> | C6 | Alam and Smith, "A Phenomenological Theory of Correlated Multiple Soft-Breakdown Events in Ultra-Thin Gate Dielectrics," 2003 IEEE, 406-411 |

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DATE CONSIDERED:

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